

[5] R. Chen, W. Zhou, M. Zhang and H-S Kwok, "High performance self-aligned top-gate ZnO thin film transistors using sputtered Al₂O₃ gate dielectric", *Thin Solid Film*, vol. 520, pp. 6681-6683, 2012.

[6] R. Chen, W. Zhou, M. Zhang, M. Wong and H-S. Kwok, "Self-Aligned Indium-Gallium-Zinc Oxide Thin-Film Transistor With Source/Drain Regions Doped by Implanted Arsenic", *IEEE Electron Device Lett.*, vol. 34, pp. 60-62, 2013.

[7] S. Li, Y. Cai, D. Han, Y. Wang, L. Sun, M. Chan and S. Zhang, "Low-Temperature ZnO TFTs Fabricated by Reactive Sputtering of Metallic Zinc Target", *IEEE Trans. Electron devices*, vol. 59, pp.2555-2558, 2012.

[8] W-S. Cheong, M-K. Ryu, J-H. Shin, S-H. Park and C-S. Hwang, "Transparent thin-film transistors with zinc oxide semiconductor fabricated by reactive sputtering using metallic zinc target", *Thin Solid Film*, vol. 516, pp. 8159-8164, 2008.